

Interactions of Chemical Mechanical Planarization Nanoparticles with Model Cell Membranes: Implications for Nanoparticle Toxicity (425.041)

PI:

- **Professor Kai Loon Chen, Geography and Environmental Engineering (DoGEE), Johns Hopkins University (JHU)**

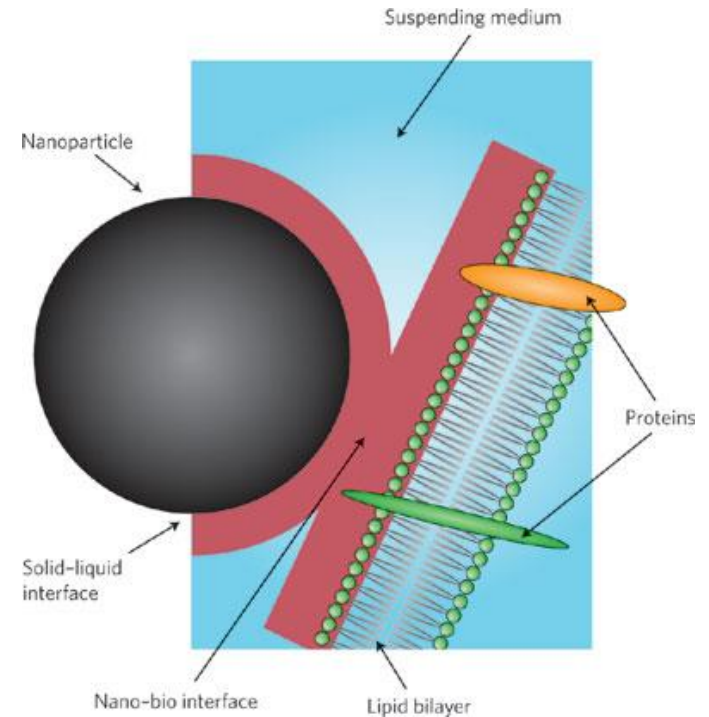
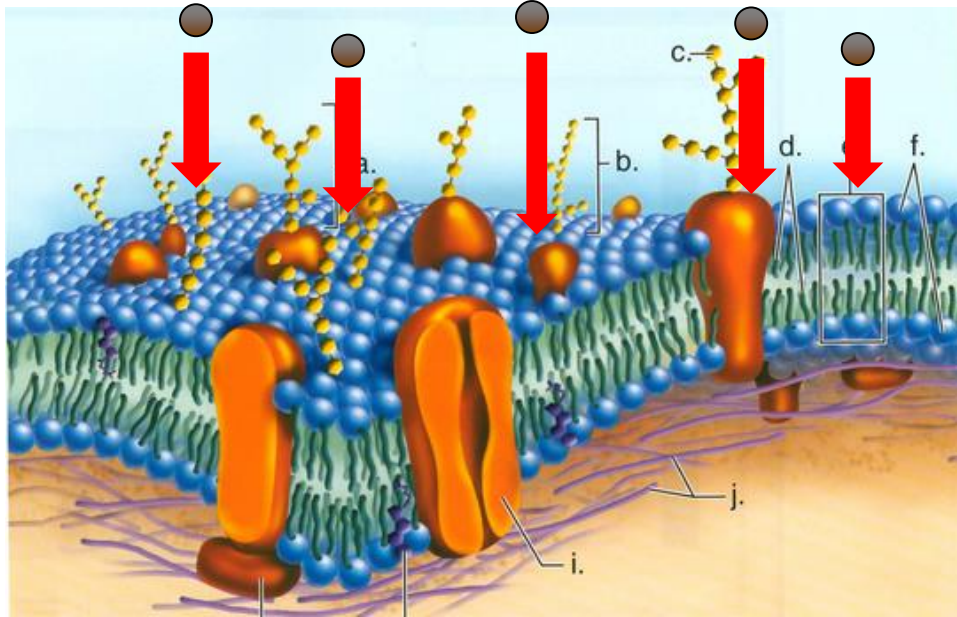
Graduate Students:

- **Peng Yi, PhD, DoGEE, JHU – currently Assistant Professor at Florida Atlantic University**
- **Khanh An Huynh, PhD, DoGEE, JHU – currently NRC research fellow at EPA**
- **Xitong Liu, second-year PhD student, DoGEE, JHU**
- **Wenyu Gu, MSE, DoGEE, JHU – currently PhD student at University of Michigan**

Cost Share (other than core ERC funding):

- **\$101,472 from Johns Hopkins University in the form of 80% of tuition for 3 years**

Objectives



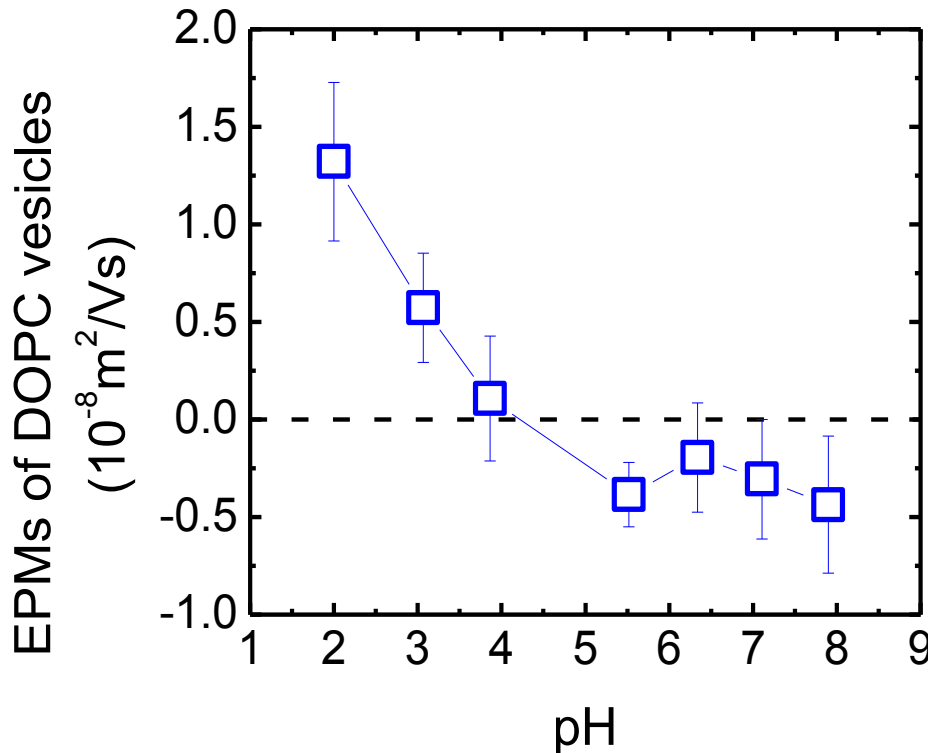
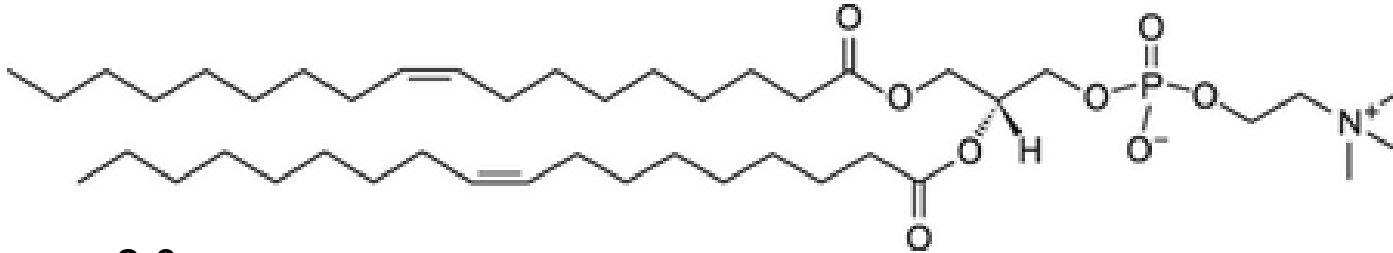
- To investigate the propensity of chemical mechanical planarization nanoparticles (silica, ceria, and alumina) to attach to model biological membranes
- To develop a rapid assay to assess the propensity of nanomaterials to absorb on biological membranes

ESH Metrics and Impact

- 1. Rapid assay for propensity of CMP particles to bind to cell membranes**
 - **Use of sensitive quartz crystal microbalance (QCM-D)**
- 2. Reduction in the use of CMP particles that bind strongly to membranes**
 - **CMP particles will be tested with binding assay before being employed in semiconductor fabrication plants**
- 3. Reduction in emission of CMP particles that bind strongly to membranes to environment**
 - **CMP nanoparticles may be replaced with other alternative materials/particles that do not strongly interact with biological membranes**

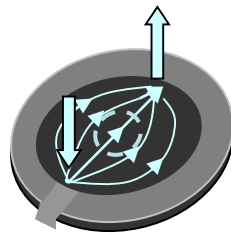
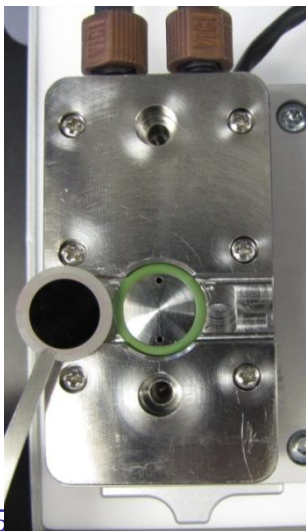
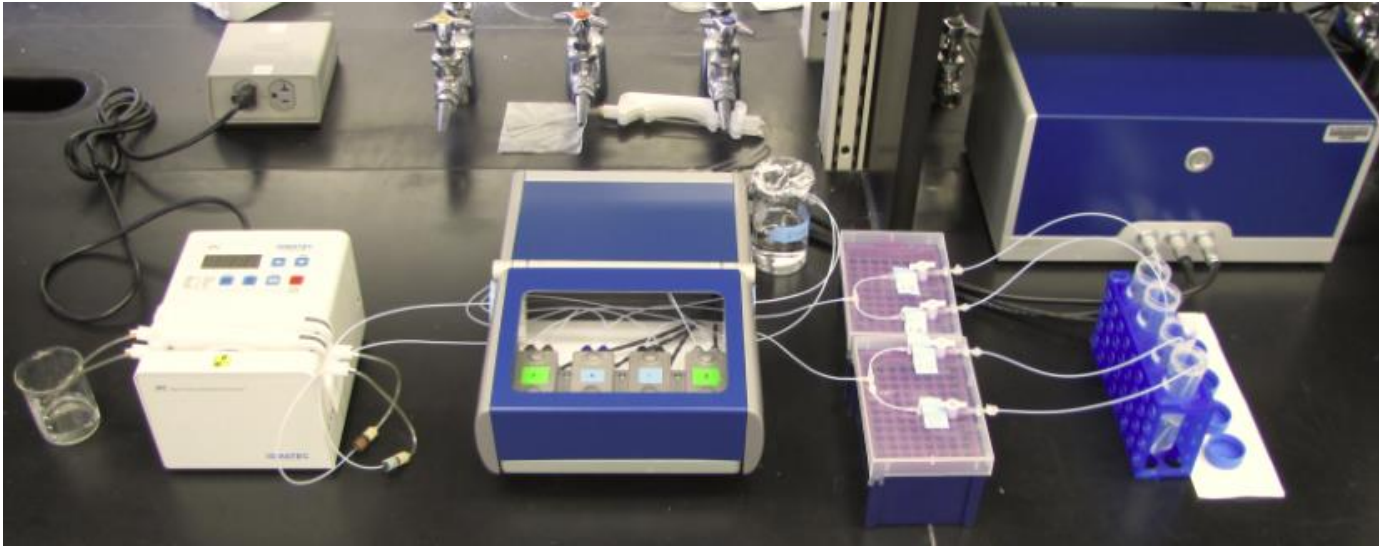
DOPC Supported Lipid Bilayers (SLBs) as Model Cell Membranes

DOPC (1,2-dioleoyl-*sn*-glycero-3-phosphocholine)



- DOPC vesicles prepared by extrusion with 50-nm membranes
- pH_{ZPC} of DOPC is about 4

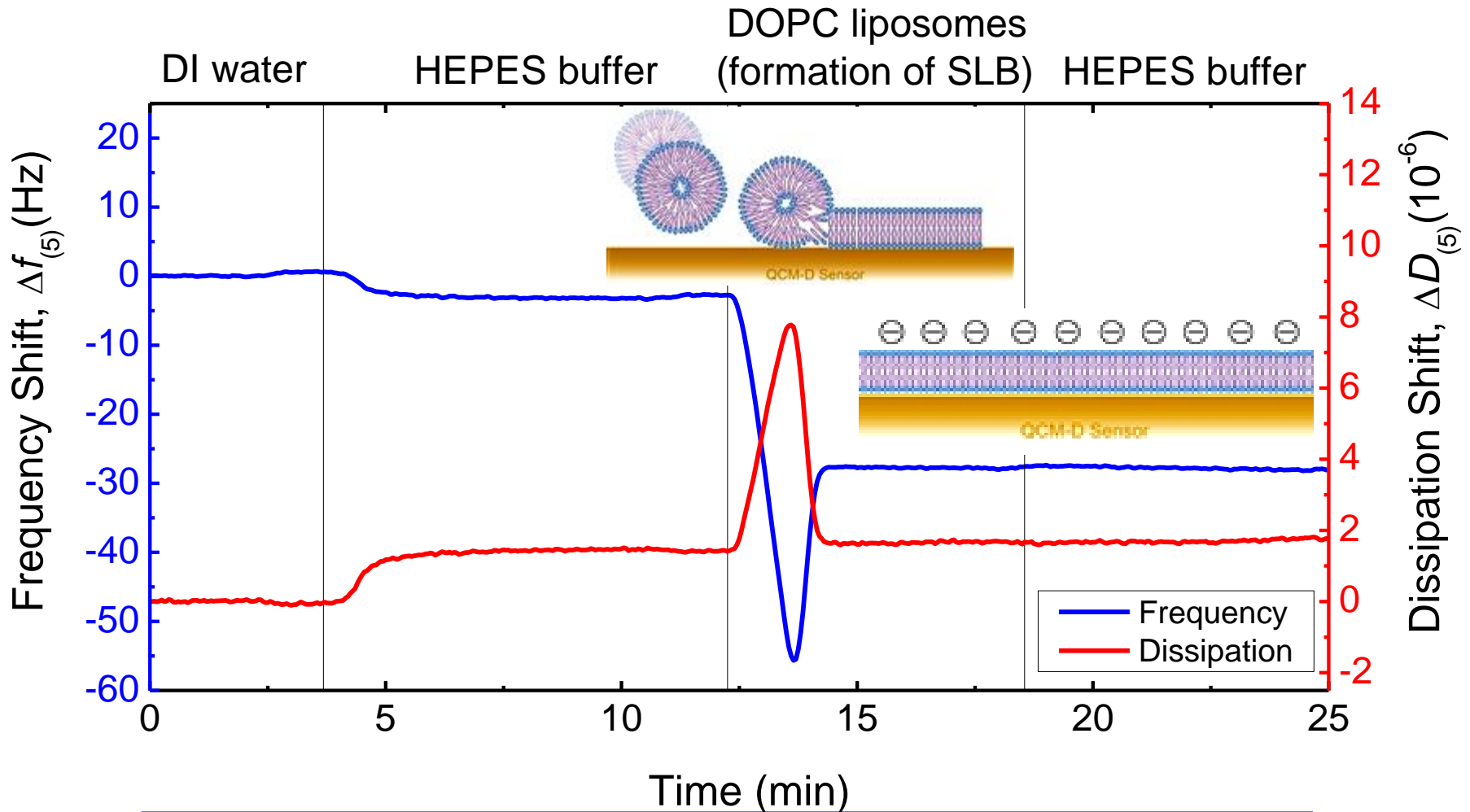
Quartz Crystal Microbalance with Dissipation Monitoring (QCM-D)



- Sensitivity of ca. 10 ng/cm^2
- Frequency, Δf – deposited mass
- Dissipation, ΔD – “softness” of deposited constituents
- Laminar flow at 0.1 mL/min
- $T = 25 \text{ }^\circ\text{C}$, $\text{pH} = 2\text{--}8$

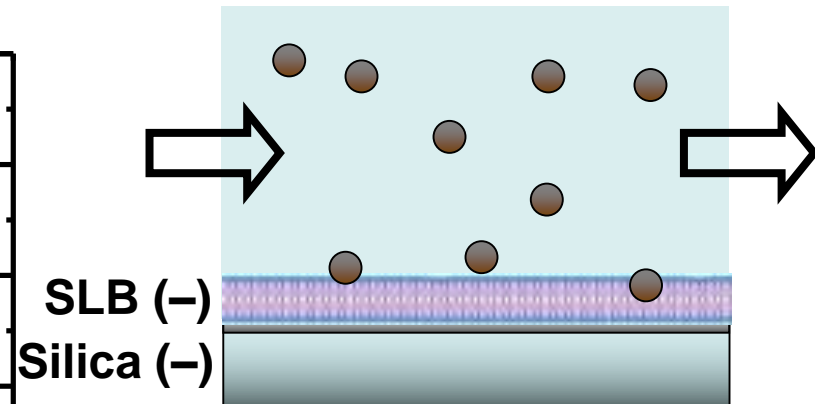
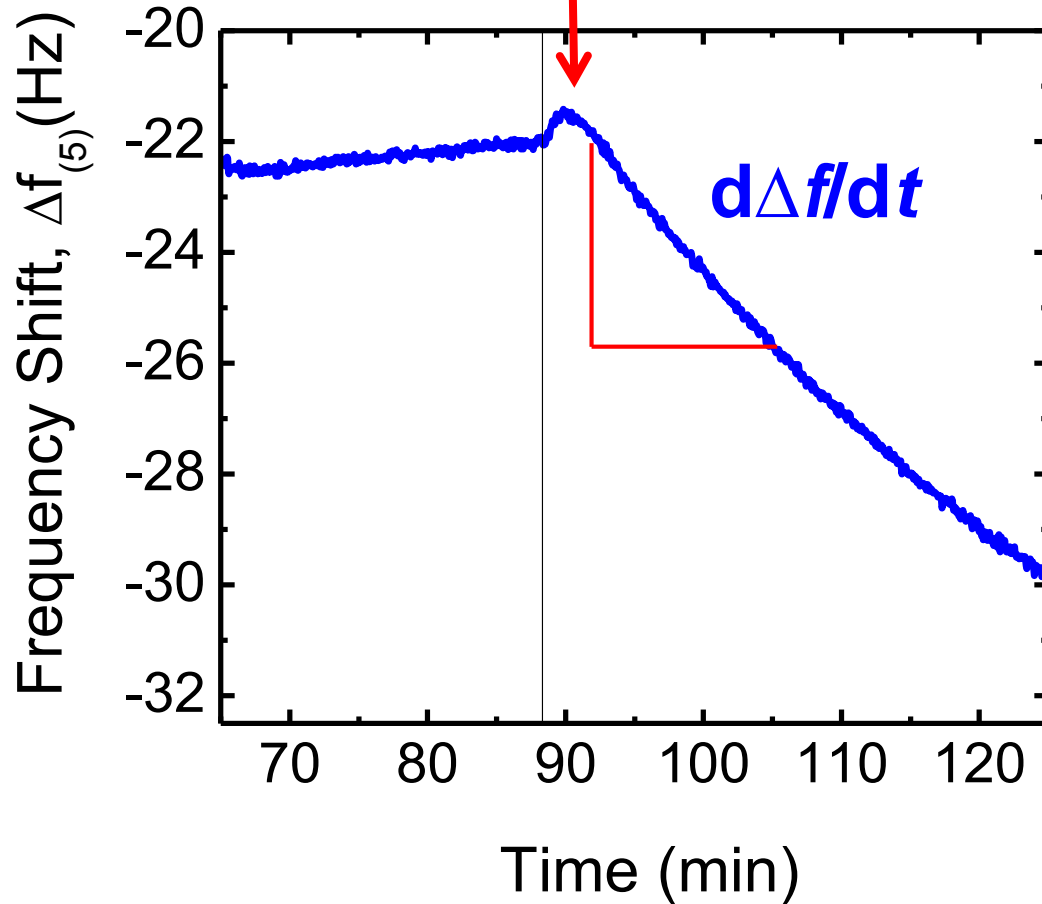
Formation of Supported Lipid Bilayers on Silica-Coated QCM-D Crystals

- Approach of Keller and Kasemo, 1998



Deposition of CMP NPs on SLBs

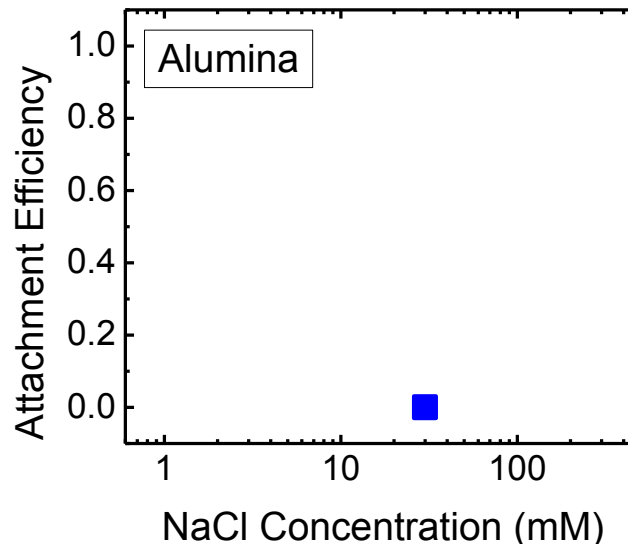
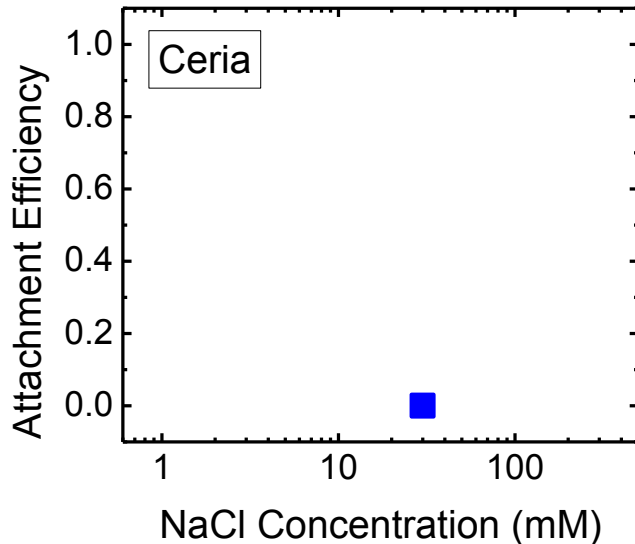
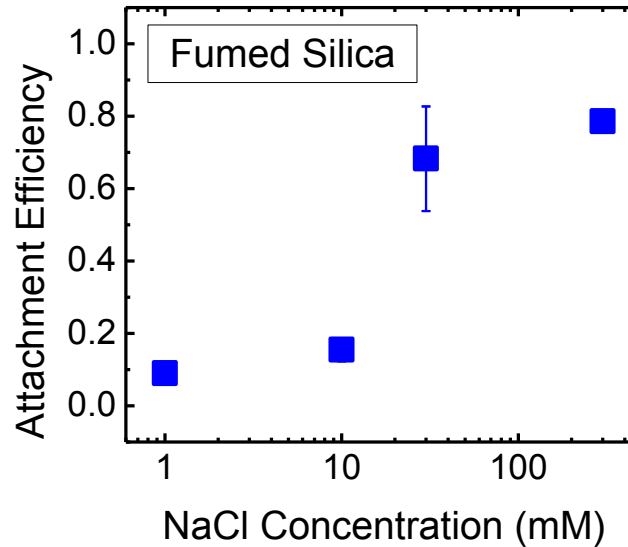
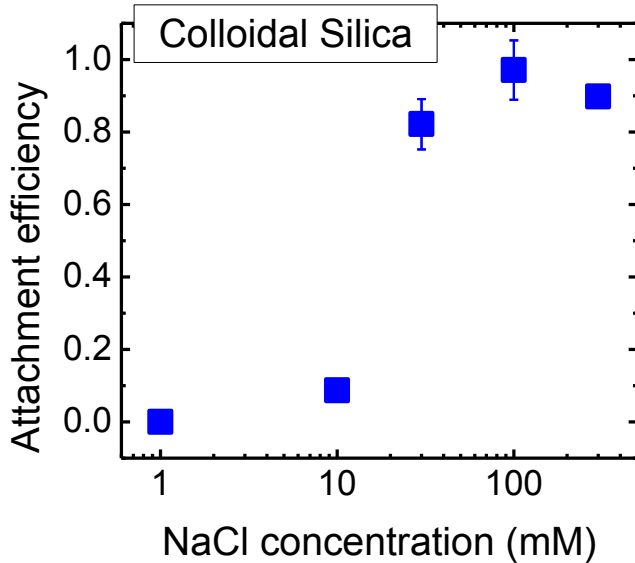
DEPOSITION



- $d\Delta f/dt$ is proportional to rate of nanoparticle deposition

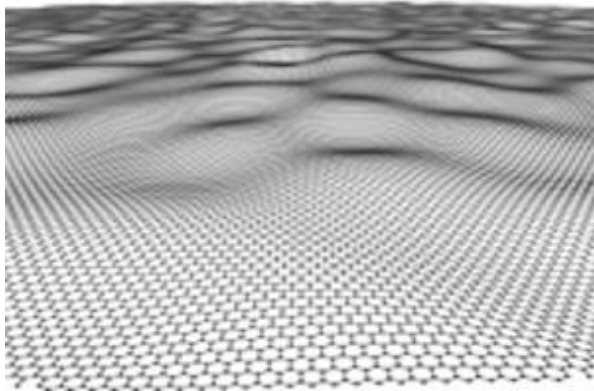
Comparing Deposition Kinetics of Cabot CMP

NPs on SLBs at pH 7.4

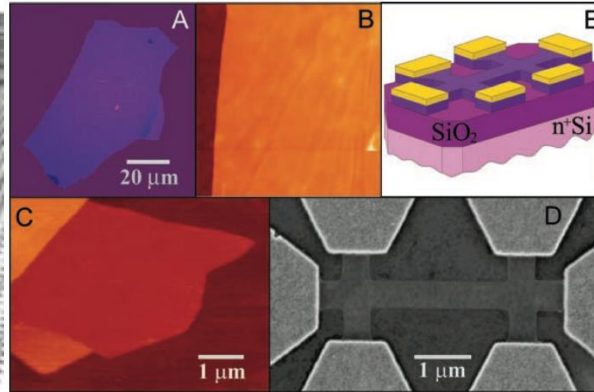


- At pH 7.4, all CMP NPs are negatively charged
- For both silica NPs, deposition kinetics increases as NaCl concentration increases
- Ceria and alumina NPs have low propensity to attach to membranes

Graphene and Graphene Oxide

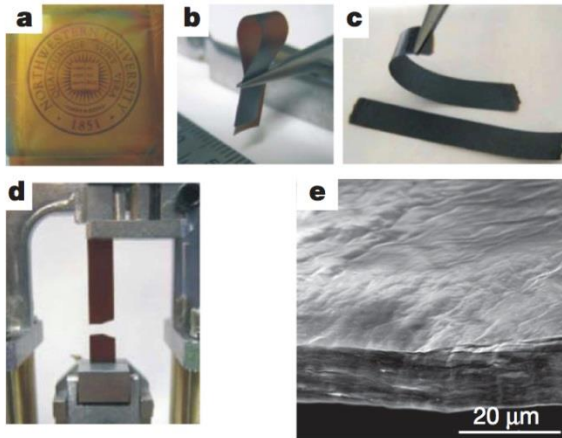


phys.org

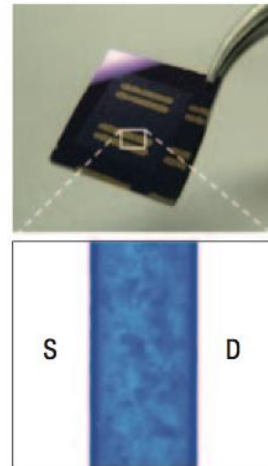


Novoselov et al., *Science*,
2004, 666-669

- Graphene
 - One layer of C atoms
 - High electrical conductivity



Dikin et al., *Nature*,
2007, 457-460

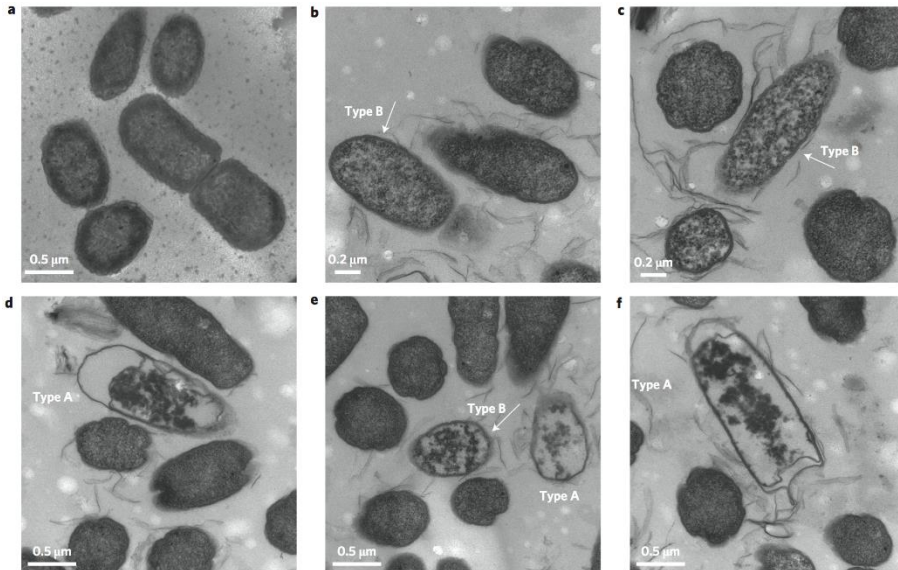


Eda et al. *Nat. Nanotechnol.*,
2008, 270-274

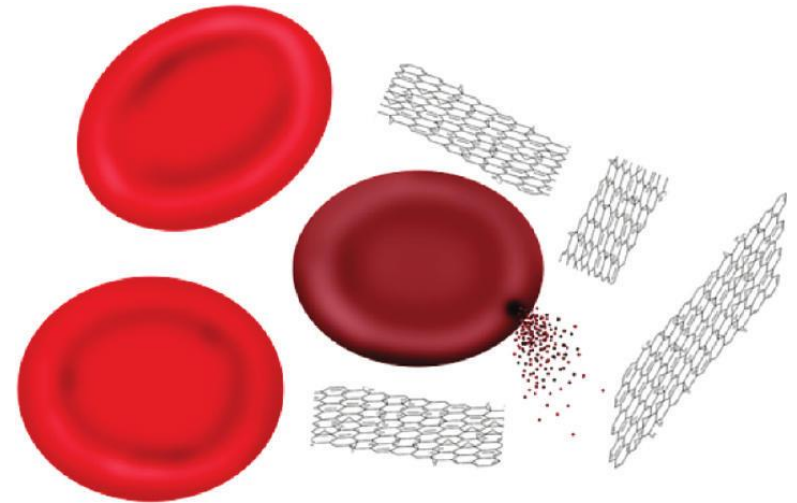
- Graphene oxide (GO)
 - Reduced to form rGO
 - Can be dispersed in water

Toxicity of Graphene Oxide

- Destructive extraction of phospholipids from membranes of *Escherichia coli* cells
- Hemolysis of red blood cells

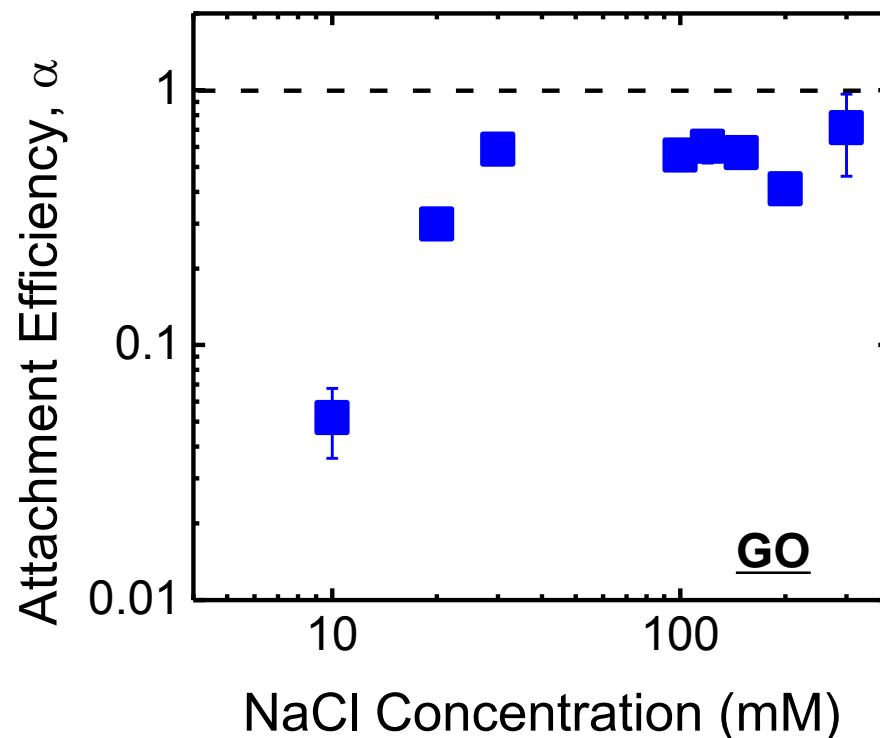
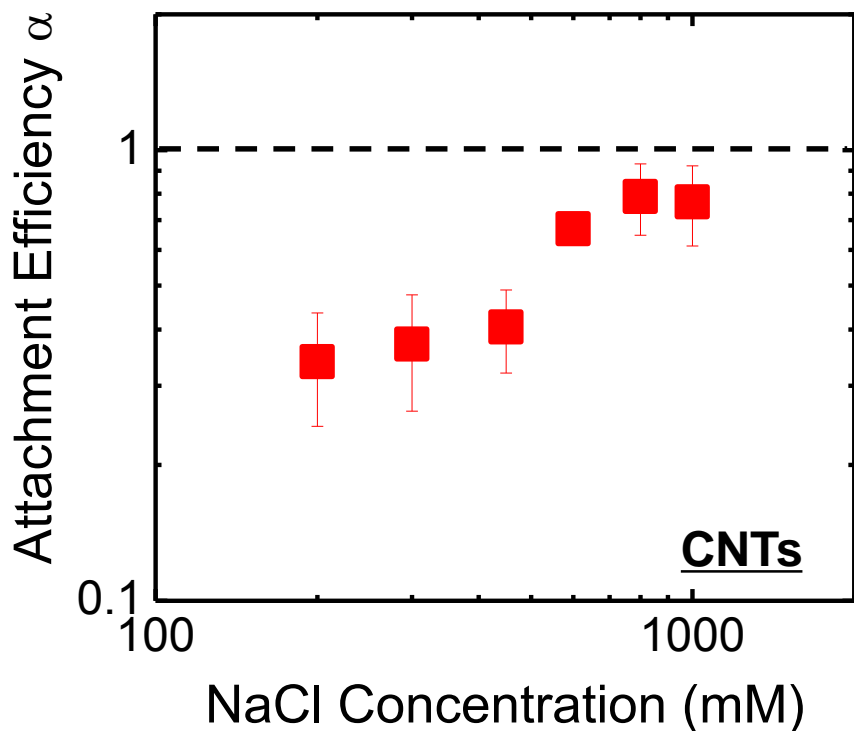


Tu et al. *Nat. Nanotechnol.*,
2013, 594-601



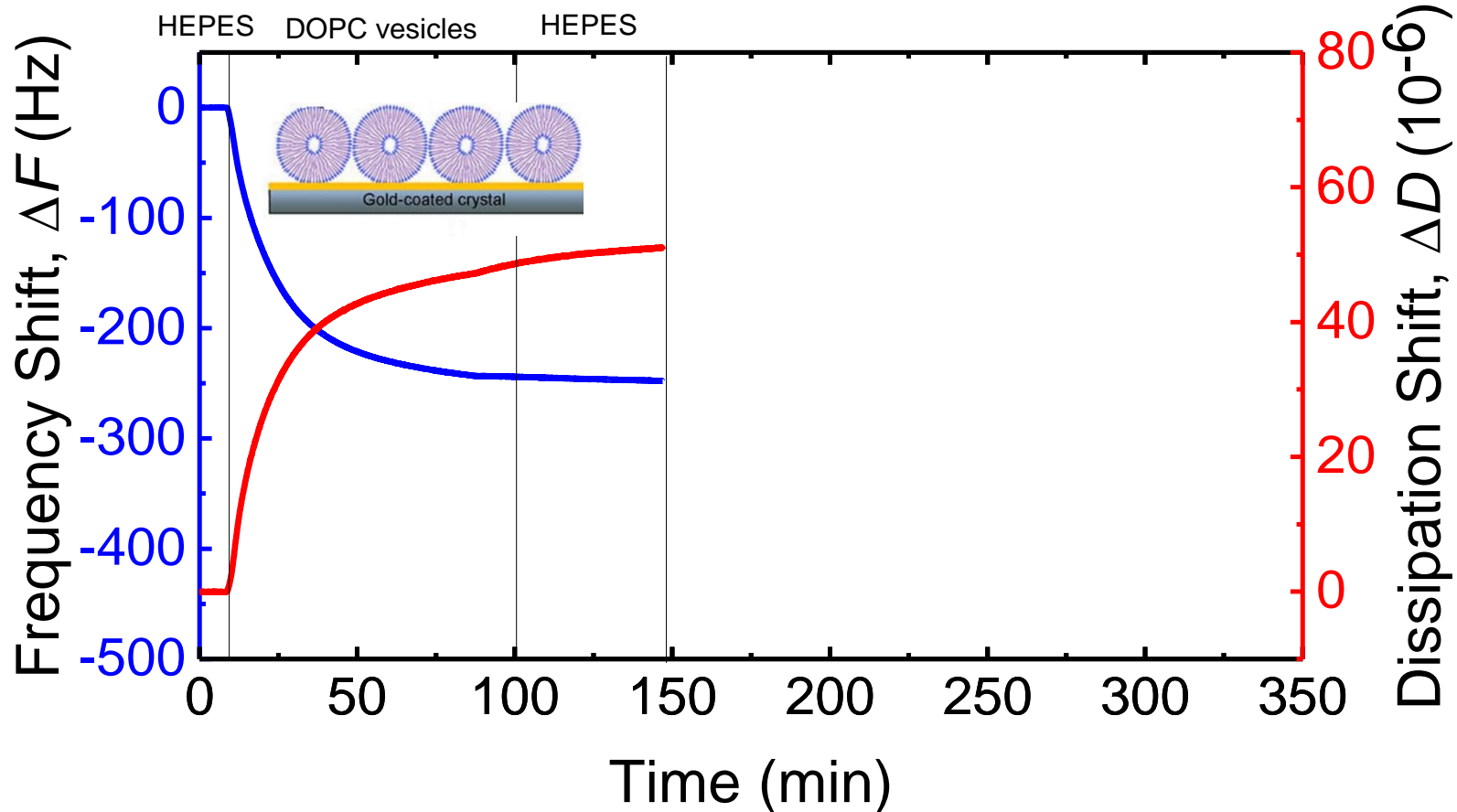
Liao et al., *ACS Appl. Mat. Interfaces*,
2011, 2607-2615

Deposition Kinetics of CNTs and GO on SLBs in NaCl

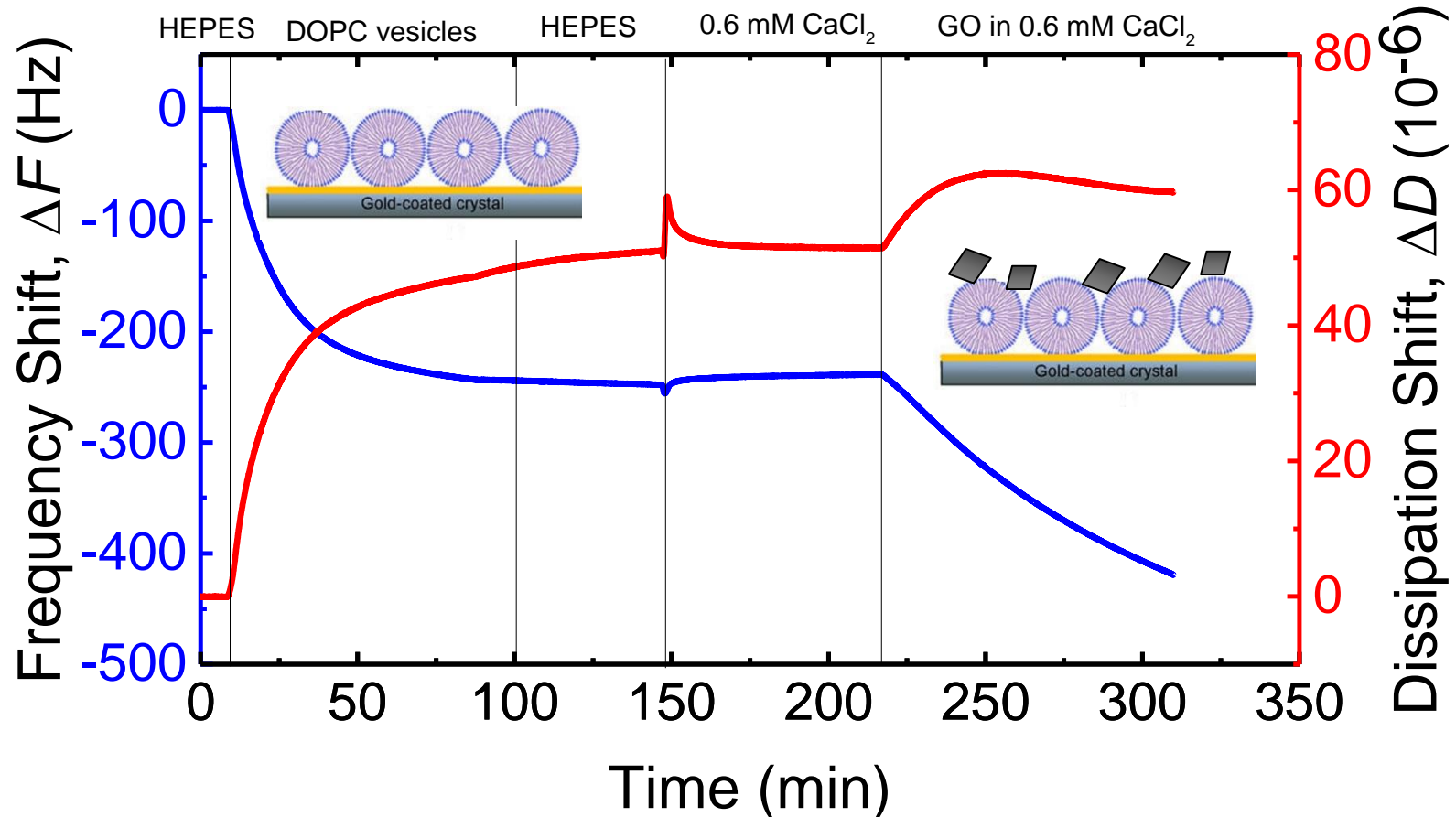


■ Attachment efficiencies of CNTs and GO lower than 1.0 even at high NaCl concentrations

Interactions of GO with Supported Vesicular Layer



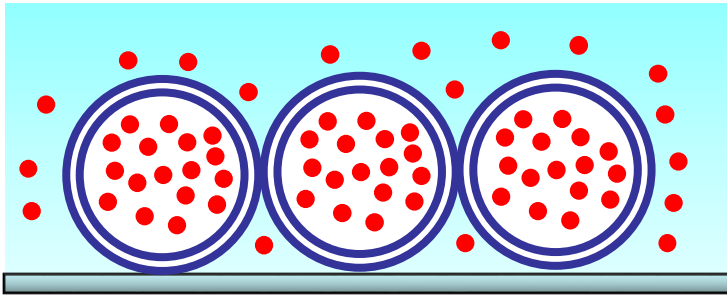
Interactions of GO with Supported Vesicular Layer



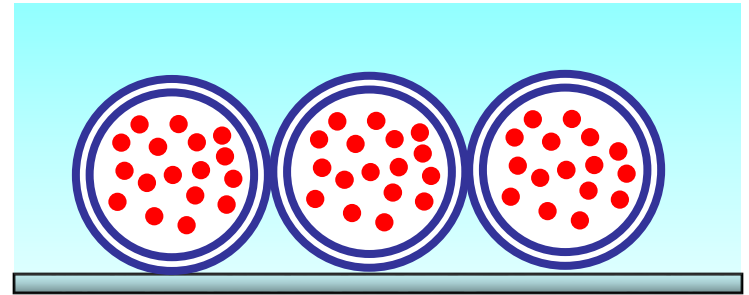
■ **GO deposited on supported vesicles; no significant rupture of vesicles**

Fluorescent Dye-Encapsulated Vesicles Deposited on QCM-D Crystals

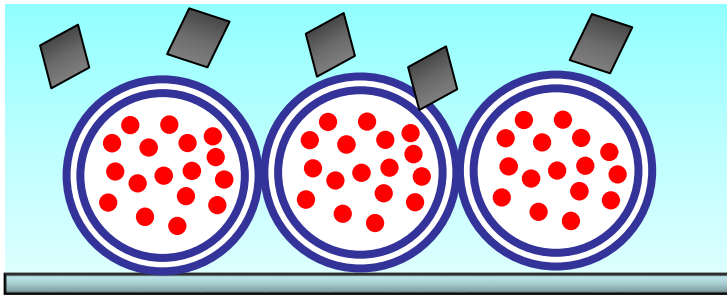
(A) Supported vesicular layers on Au



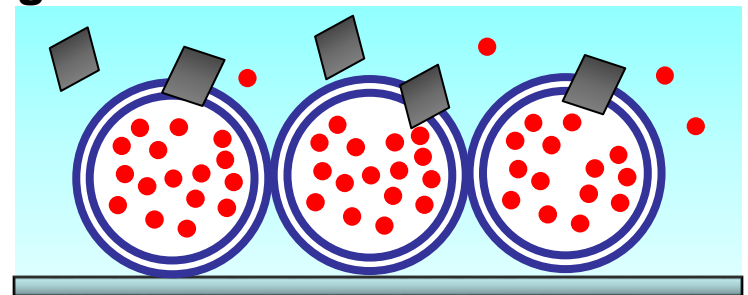
(B) Buffer rinse to remove external dye



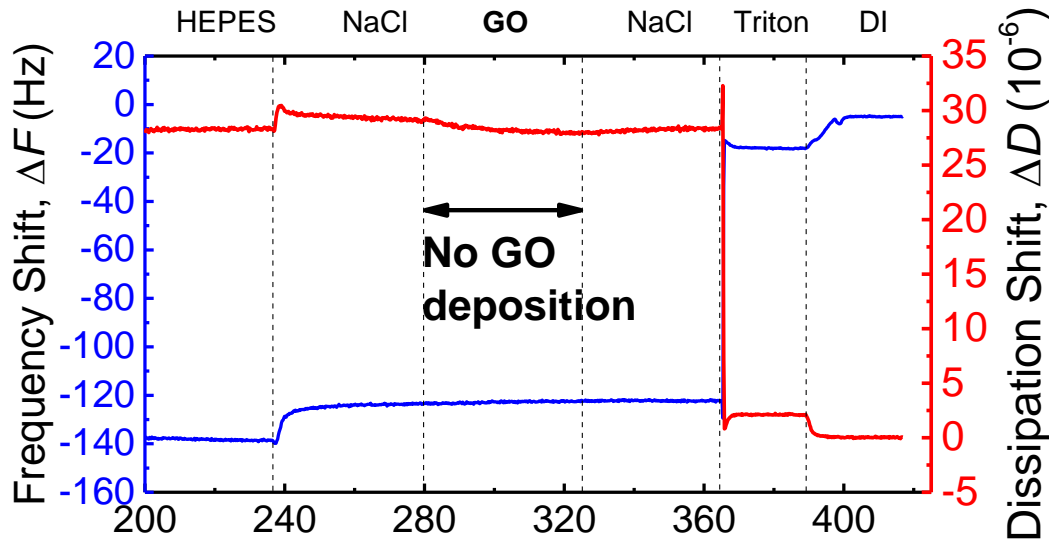
(C) Introduce GO



(D) Monitor dye leakage and QCM-D signal

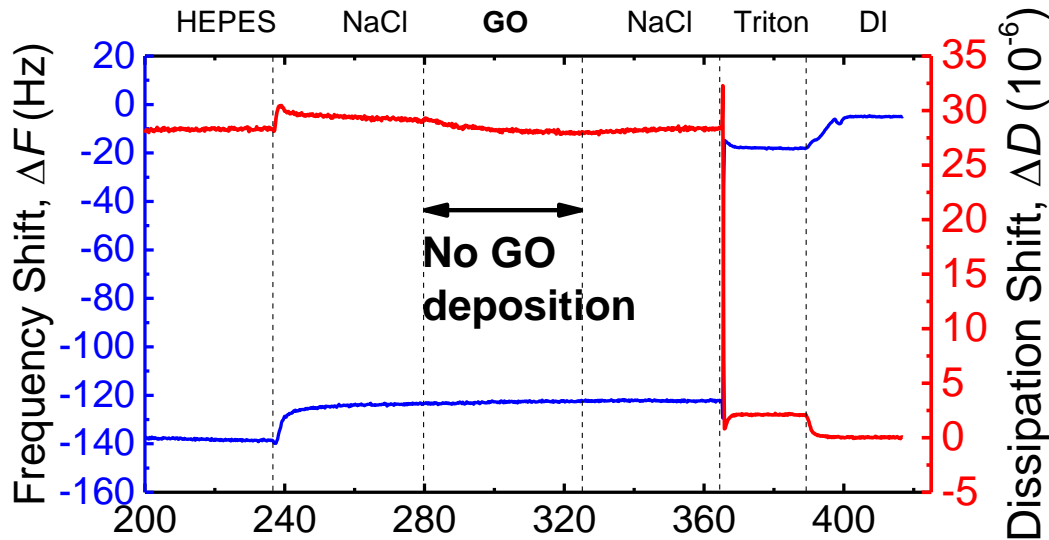


Exposure of Supported Vesicles to GO under Unfavorable Deposition Conditions



■ GO does not deposit on vesicles at 1 mM NaCl

Exposure of Supported Vesicles to GO under Unfavorable Deposition Conditions

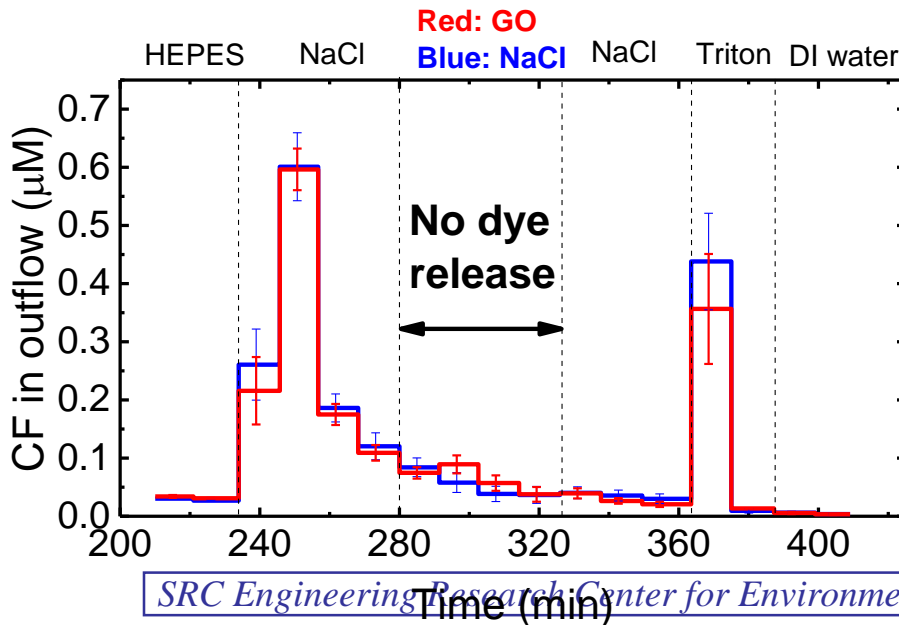


■ GO does not deposit on vesicles at 1 mM NaCl

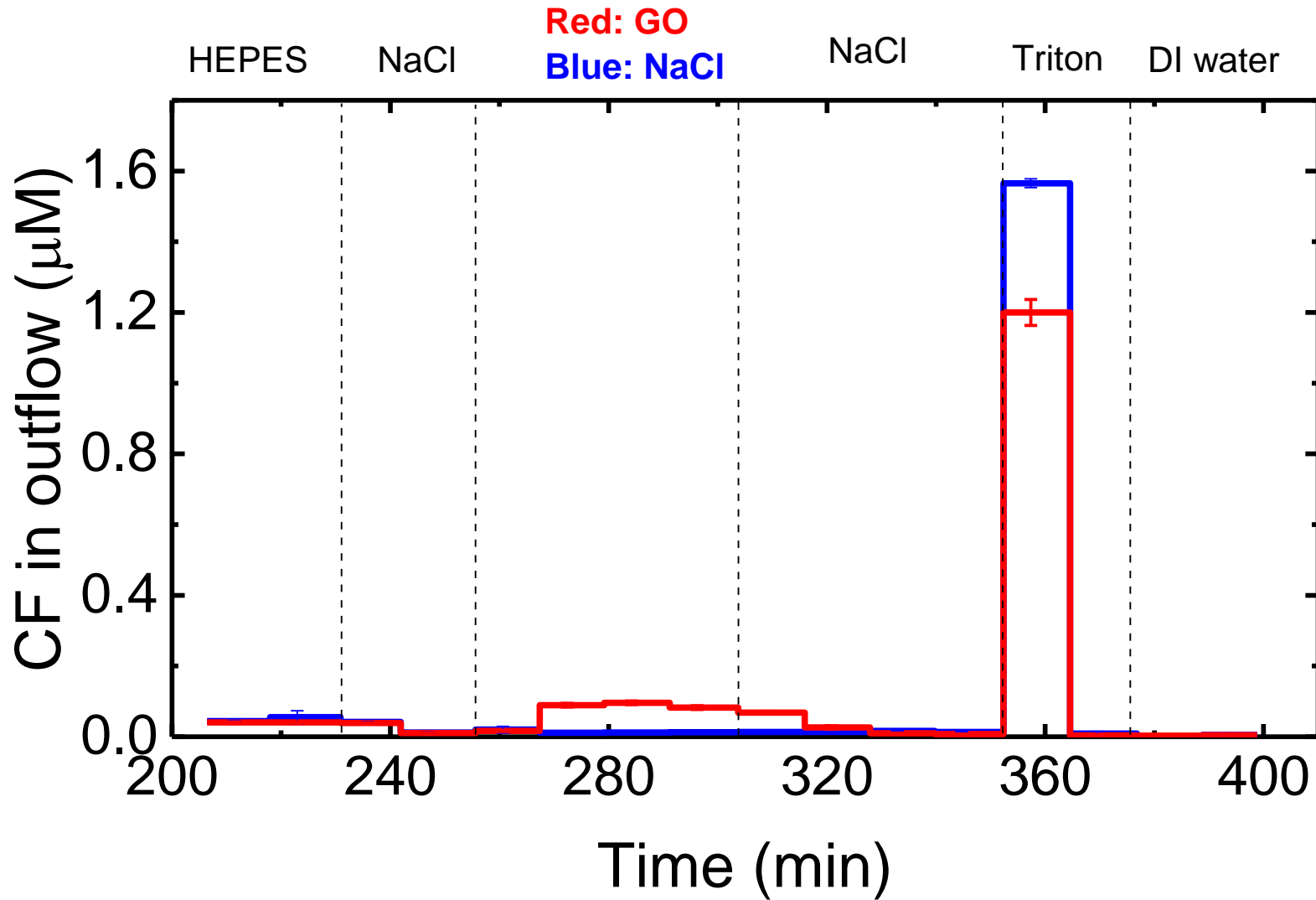
■ Carboxyfluoresceine (CF)

■ Emission at 517 nm

■ No significant dye release when vesicles are exposed to GO

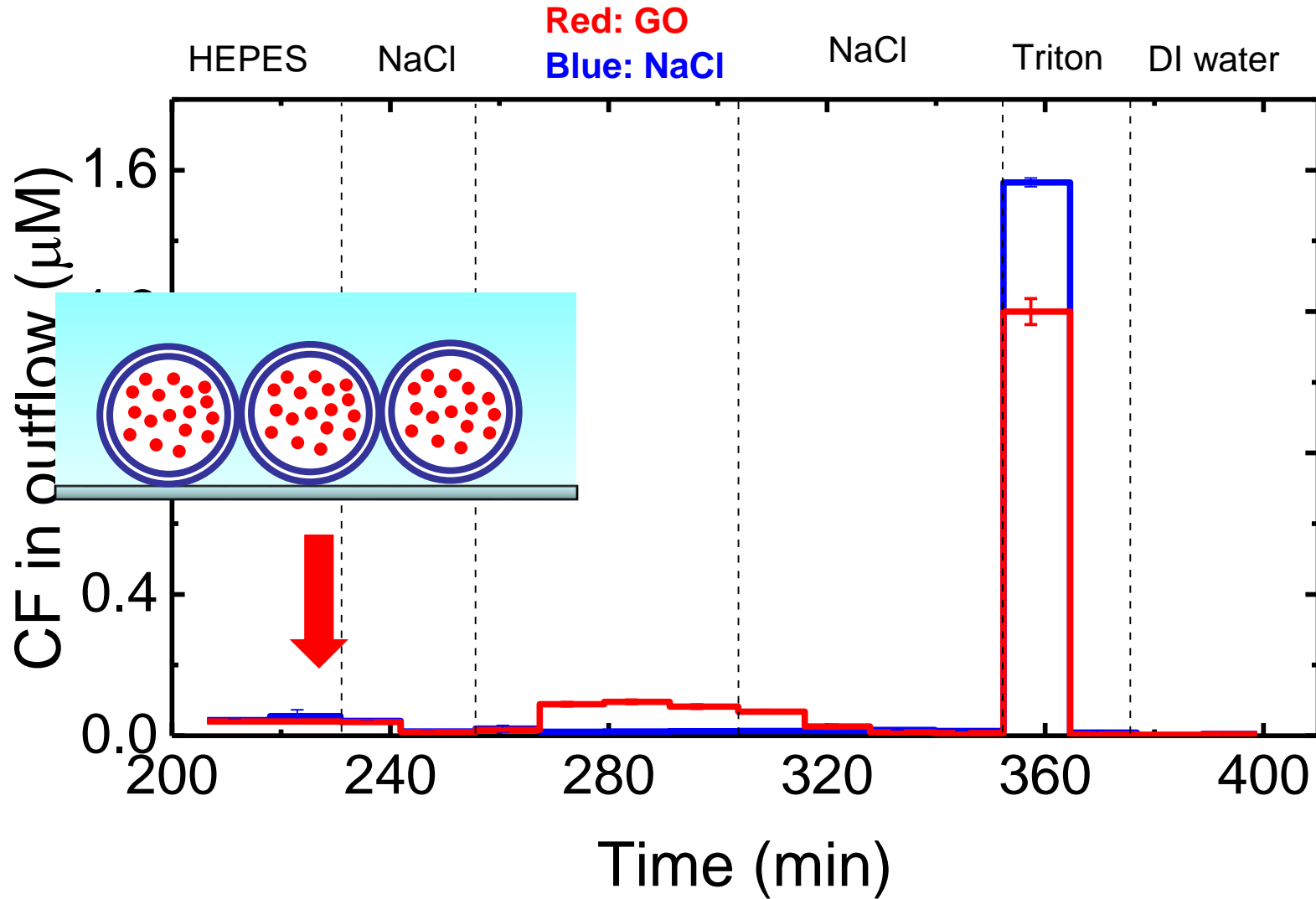


Exposure of Vesicles to GO at 150 mM NaCl

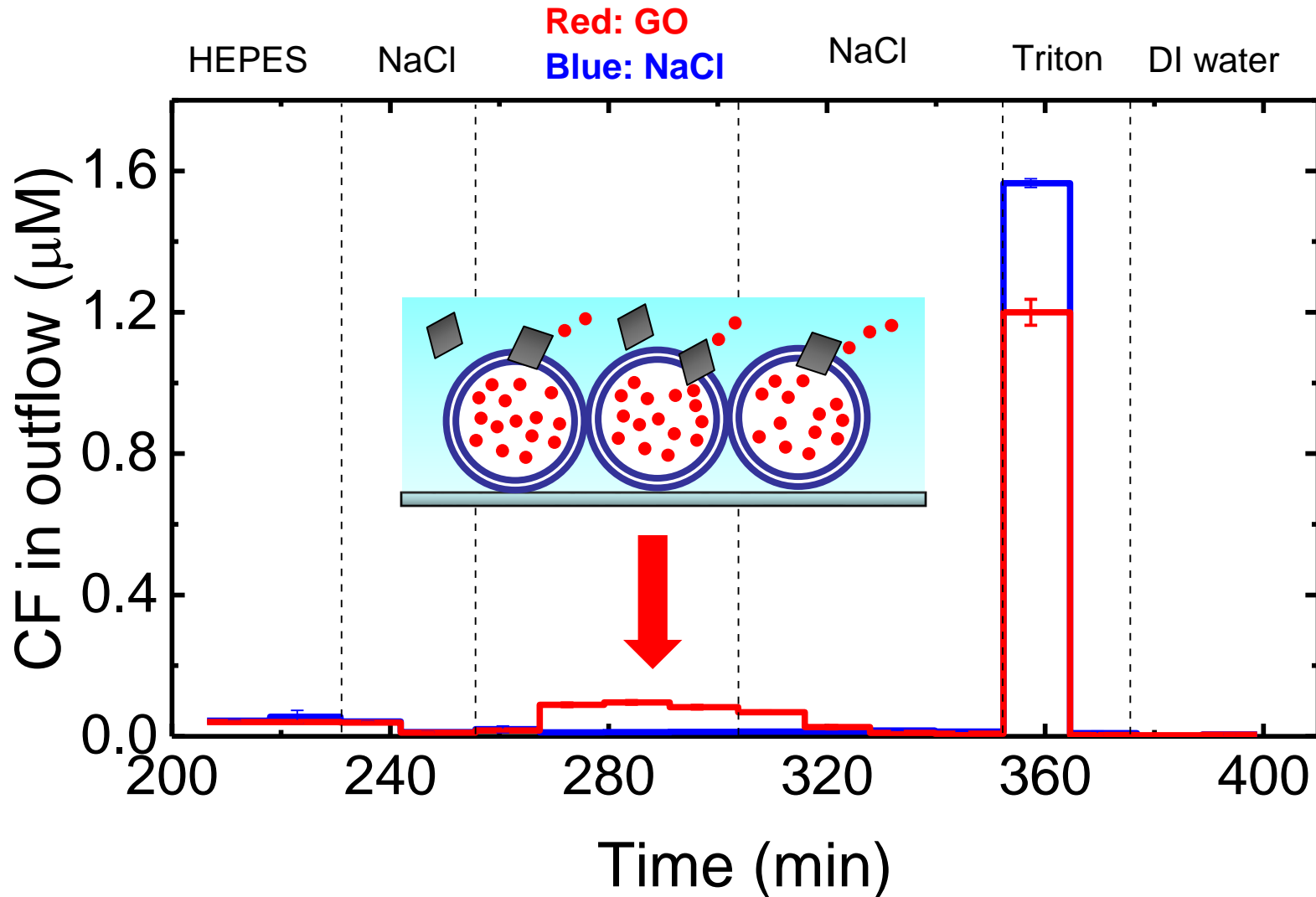


■ GO undergoes favorable deposition at 150 mM NaCl

Exposure of Vesicles to GO at 150 mM NaCl

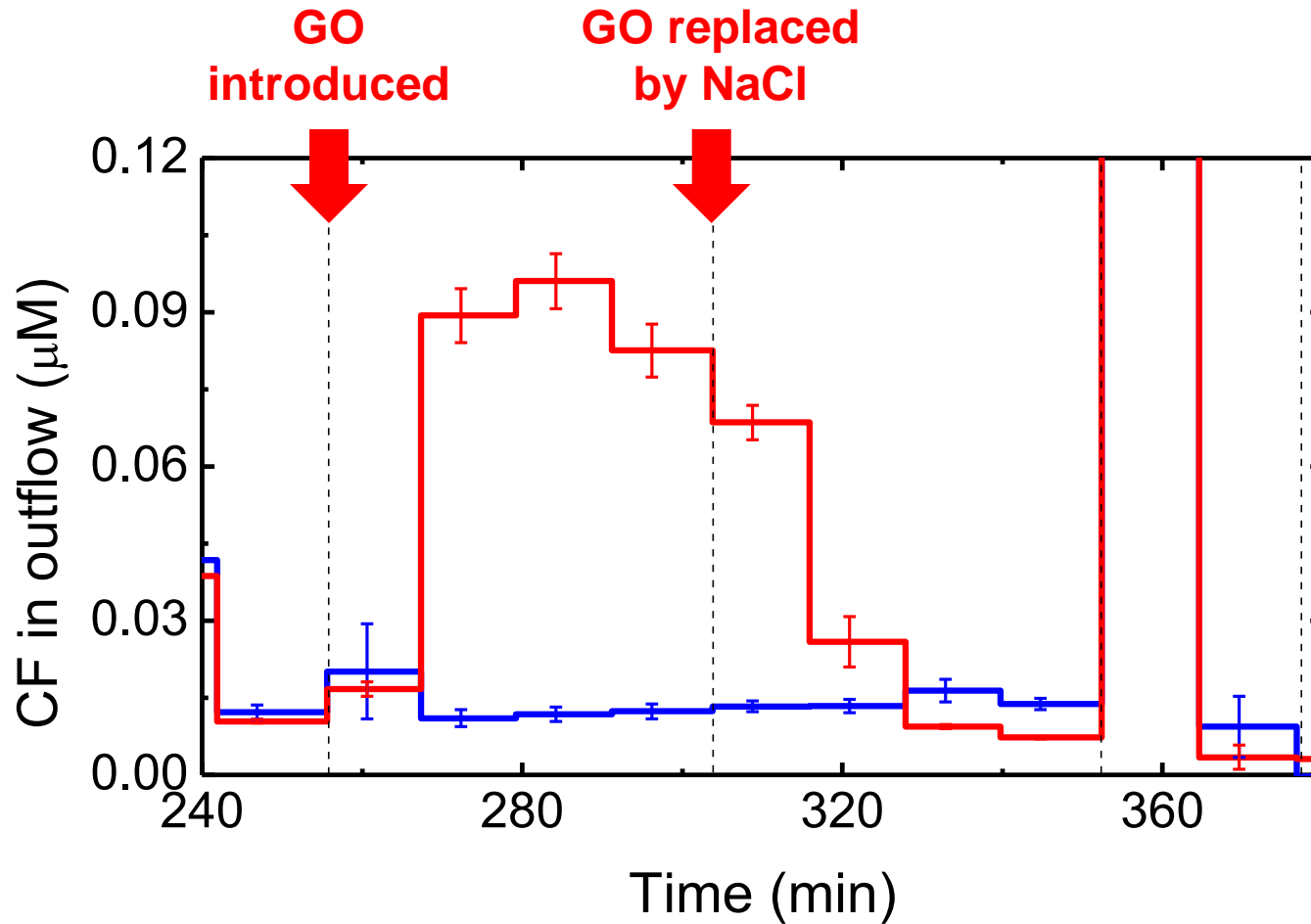


Exposure of Vesicles to GO at 150 mM NaCl



■ Dye release upon exposure to GO at 150 mM NaCl

Exposure of Vesicles to GO at 150 mM NaCl



■ Dye release decreases when GO is replaced by NaCl solution, indicative of hole healing

Summary of Current Findings

- **Deposition of carbon-based nanomaterials on model biological membranes is controlled by electric double layer interactions**
- **Nanoparticle–membrane interactions are strongly influenced by pH and electrolyte concentrations**
- **Favorable attachment is not observed at high NaCl concentrations possibly due to repulsive hydration forces**
- **GO resulted in some dye release from vesicles, likely due to hole formation on vesicles**
- **Holes on vesicles seem to heal in the absence of GO**

Industrial Interactions and Technology Transfer

- **Dr. Chen, together with the other PIs from the SRC ERC, have obtained representative CMP NPs from Cabot Microelectronics in order to investigate their propensity to attach to biological membranes**
- **Dr. Chen, together with the other PIs, have closely interacted with SRC industrial members (David Speed from IBM and Mansour Moinpour from Intel) regarding research progress**
- **SRC industrial members will be updated on the development of the QCM-D as a rapid and online binding assay for nanomaterials**
- **SRC industrial members will be informed of the types of CMP NPs that have a strong propensity to bind to cell membranes based on the research findings in Dr. Chen's lab**
- **Dr. Chen's group presented 3 ERC/SRC teleseminars**

Future Plans

Next Year Plans

- **Continue to investigate the propensity of GO and CMP NPs to penetrate or disrupt model biological membranes**
- **Develop a rapid assay using the QCM-D to evaluate the propensity of nanomaterials to disrupt biological membranes**

Long-Term Plans

- **Examine the interactions of GO and CMP NPs with proteins and the effects of protein corona on NP interactions with model cell membranes**

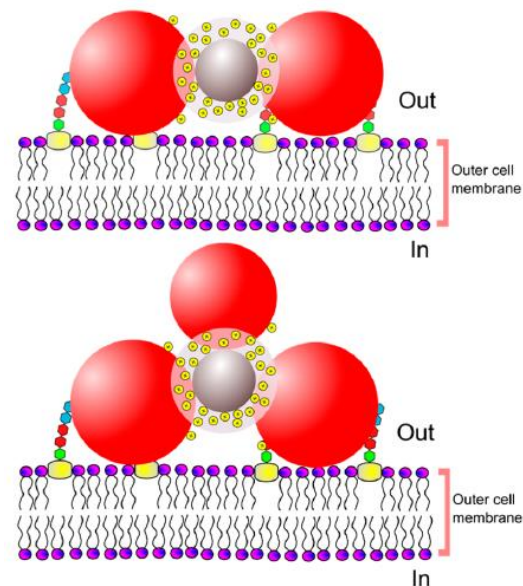
Publications, Presentations, and Recognitions/Awards

• Publications

- Four papers published in *Environmental Science & Technology*, including a feature article featured on the cover of *ES&T*, one paper published in *ES&T Letters*, and one in *Environmental Science: Processes and Impacts*
- One other manuscript just submitted

• Presentations

- Dr. Chen has been invited to give talks at seven universities, IBM, ACS Meeting at San Francisco, and US Environmental Protection Agency
- 9 oral presentations at conferences

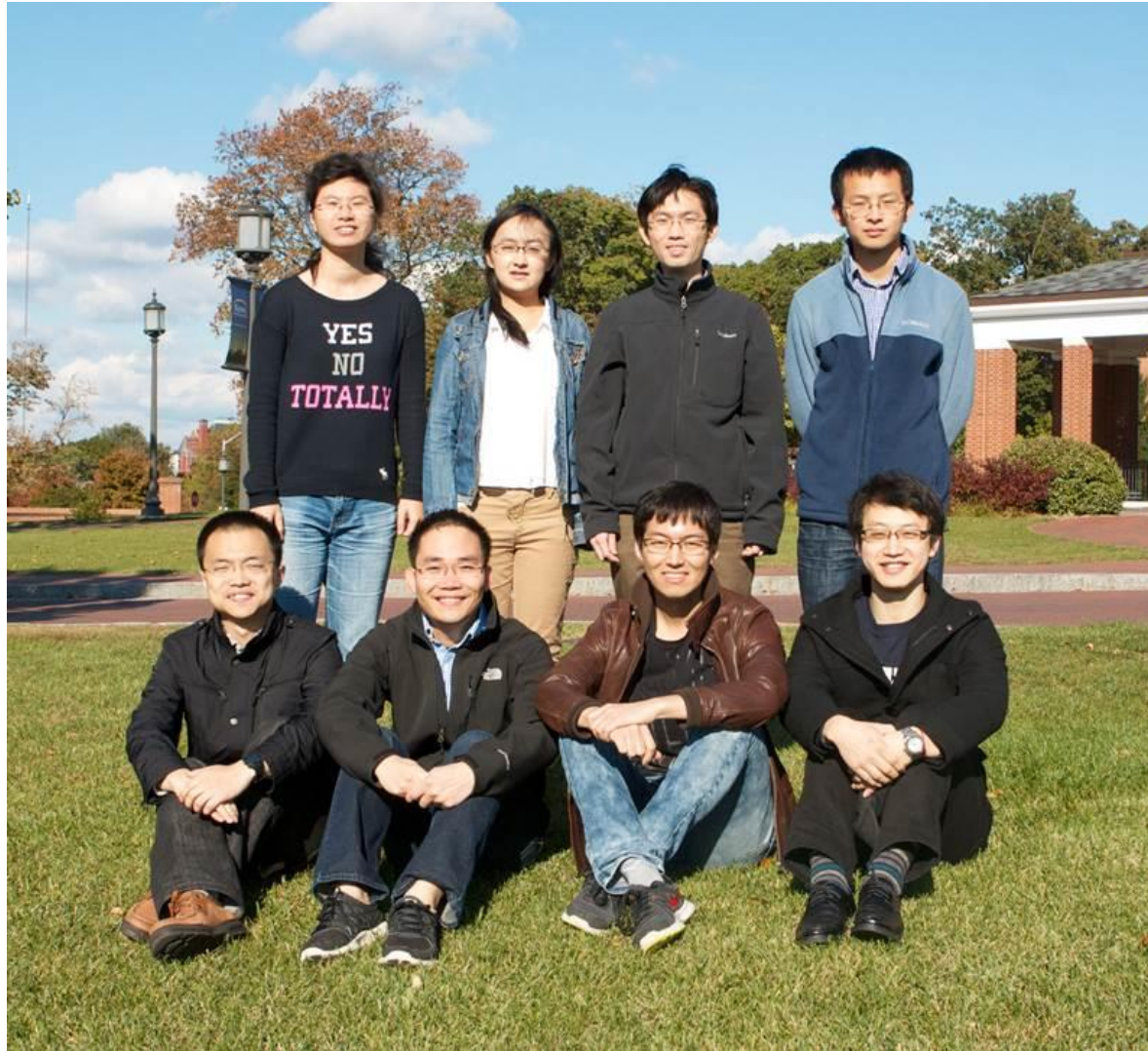


SRC Engineering Research Center for Environmentally Benign Semiconductor Manufacturing

Publications, Presentations, and Recognitions/Awards

- **Recognitions/Awards**
 - **Dr. Chen was invited to give a keynote talk at the International Water Association (IWA) Symposium on Environmental Nanotechnology in Nanjing, China**
 - **Peng Yi and Khanh An Huynh received the prestigious C. Ellen Gonter Environmental Chemistry Awards from the American Chemical Society Division of Environmental Chemistry**
 - **Khanh An Huynh and Xitong Liu received student awards from the Sustainable Nanotechnology Organization**
- **Students**
 - **2 Ph.D. students graduated: Peng Yi (2013) and Khanh An Huynh (2014)**
 - **1 MSE student graduated: Wenyu Gu (2013)**

Thank you!



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SRC Engineering Research Center for Environmentally Benign Semiconductor Manufacturing